ツン 晨 氏 名 池 授 与 学 位 博士 (工学) 学位授与年月日 平成27年3月25日 学位授与の根拠法規 学位規則第4条第1項 東北大学大学院工学研究科(博士課程)材料システム工学専攻 研究科、専攻の名称 学位論文題目 Preparation of Li-Al-O and Na-Al-O System Oxide Films by Laser Chemical Vapor Deposition (レーザー化学気相析出法による Li-Al-O 系および Na-Al-O 系酸化物膜の合成) 指 教 員 東北大学教授 後藤 論文審查委員 主査 東北大学教授 後藤 東北大学教授 山根 久典 成島 尚之 東北大学教授

# 論文内容要旨

#### **Chapter 1 Introduction**

In this chapter, the composites in Li-Al-O and Na-Al-O systems were introduced and the objectives of this research were presented. The Li-Al-O system has three compounds of LiAl<sub>5</sub>O<sub>8</sub>, LiAlO<sub>2</sub> and Li<sub>5</sub>AlO<sub>4</sub>. LiAl<sub>5</sub>O<sub>8</sub> doped with rare-earth or transition ions is fine color emitting phosphors. LiAlO<sub>2</sub> attracts increasing attention as a potential substrate for growing GaN semiconductor due to low lattice mismatch and removability. Li<sub>5</sub>AlO<sub>4</sub> shows high reactivity with water (H<sub>2</sub>O) and carbon dioxide (CO<sub>2</sub>) in atmosphere because of high lithium content. It is deemed to be a suitable material for humidity sensor and CO<sub>2</sub> captor. NaAlO<sub>2</sub>, NaAl<sub>6</sub>O<sub>9.5</sub> and Na- $\beta$ -alumina are included in Na-Al-O system. NaAlO<sub>2</sub> received much attention as a heterogeneous base catalyst for production of biodiesel. NaAl<sub>6</sub>O<sub>9.5</sub> is metastable and transforms toward the  $\beta$ -alumina at elevated temperatures. Na- $\beta$ -alumina is well-known as an excellent solid electrolyte in Na-ion battery. My present study is aimed to preparing these useful materials in the form of film by laser CVD and investigating their electrical properties.

# **Chapter 2 Preliminary investigation**

This chapter is focused on investigating the discovery history of  $\beta$ -alumina, crystal structures of Li-Al-O and Na-Al-O composites and previous preparations of them. The problems and solution on the preparation of Li-Al-O and Na-Al-O films for present status were expatiated. Beta alumina was first reported by Rankin and Merwin in 1916. Kummer et al. investigated the details of ionic diffusion in beta alumina and discovered the remarkably high conductivity of sodium ions in 1967, which directly inspired the concept of high-temperature sodium batteries. Reducing the beta alumina thickness to micron range will result in a significant drop in area specific resistance. However,  $\beta$ -alumina films have never been obtained by CVD because of high crystallization temperature, high vapor pressure of Li/Na and high reactivity of Li/Na precursor. Due to the same reasons, other Li-Al-O and Na-Al-O composites in the form of film have been never prepared.

Thus, decreasing the preparation temperature is probably a necessary step to prepare Li-Al-O and Na-Al-O films. Laser chemical vapor deposition (laser CVD) is a deposition technique for films of various materials by introducing activated field with laser irradiation for chemical reaction. The chemical reaction on the substrate surface was activated greatly by laser, which decreased the preparation temperature and accelerated the deposition of films.

#### Chapter 3 Preparation of Li-Al-O films by laser CVD

Li–Al–O films were prepared on AlN substrates by laser CVD, as shown in Figure 1. The parameters of deposition temperature ( $T_{\rm dep}$ ), molar ratio of Li/Al ( $R_{\rm Li/Al}$ ) and total pressure ( $P_{\rm tot}$ ) were adjusted to construct the specific films. Single-phase α-LiAl<sub>5</sub>O<sub>8</sub> films were obtained at  $T_{\rm dep}=1107$ –1280 K and  $R_{\rm Li/Al}=0.1$ –2.9. By decreasing  $T_{\rm dep}$  to 1003–1273 K and increasing  $R_{\rm Li/Al}$  to 0.4–6.1, the γ-LiAlO<sub>2</sub> phase was co-deposited with the α-LiAl<sub>5</sub>O<sub>8</sub> phase. Single-phase γ-LiAlO<sub>2</sub> films were obtained at  $T_{\rm dep}=984$ –1238 K and  $R_{\rm Li/Al}=0.9$ –10.6. A further decrease in  $T_{\rm dep}$  to 940–1060 K and increase in  $T_{\rm dep}=0.2$ –10.6 resulted in the co-deposition of γ-LiAlO<sub>2</sub> and β-Li<sub>5</sub>AlO<sub>4</sub> phases. Single-phase β-Li<sub>5</sub>AlO<sub>4</sub> films were obtained at  $T_{\rm dep}=0.2$  K and  $T_{\rm Li/Al}=0.2$  An amorphous film was prepared at  $T_{\rm dep}=0.2$  K, which was crystallized to α-Al<sub>2</sub>O<sub>3</sub> after annealing at 1273 K for 2 h. At 833 K, no film was obtained, irrespective of the  $T_{\rm Li/Al}$  value.

Various textures of Li-Al-O films were formed after deposition, as shown in Figure 2. The surface of a single-phase α-LiAl<sub>5</sub>O<sub>8</sub> film prepared at  $T_{\text{dep}} = 1280$  K and  $R_{\text{Li/Al}} = 1.6$  showed faceted grains with pyramidal and polygonal shapes (Fig. 2(a)). The cross-section was columnar (Fig. 2(b)). At  $T_{\text{dep}} = 1183$  K and  $R_{\text{Li/Al}} = 1.9$ , the surface of a single-phase (001)-γ-LiAlO<sub>2</sub> film consisted of pyramidal grains, and the cross-section was an elongated columnar structure (Fig. 2(c), (d)). At  $T_{\text{dep}} = 923$  K and  $R_{\text{Li/Al}} = 11.4$ , a single-phase β-Li<sub>5</sub>AlO<sub>4</sub> film had a rough fluffy surface and consisted of columns larger than 2 μm (Fig. 2(e), (f)).

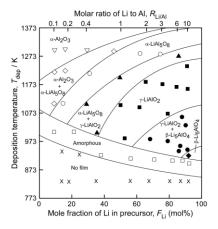


Fig. 1 Effects of  $T_{\text{dep}}$  and  $R_{\text{Li/Al}}$  on the crystalline phases of Li–Al–O films prepared by LCVD.

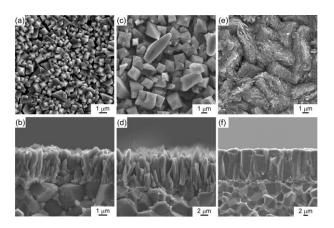


Fig. 2 Surface and cross-sectional microstructures of (a, b) LiAl<sub>5</sub>O<sub>8</sub> film, (c, d) LiAlO<sub>2</sub> film, and (e, f) Li<sub>5</sub>AlO<sub>4</sub> film.

#### Chapter 4 Preparation of Na-Al-O films by laser CVD

NaAlO<sub>2</sub>, NaAl<sub>6</sub>O<sub>9.5</sub> and Na-β-alumina films were prepared on AlN substrate by laser CVD. To obtain as-deposited Na-β-alumina film, the disadvantage of high vapor pressure of Na was overcome by extremely increasing  $R_{\text{Na/Al}}$  and  $P_{\text{tot}}$ , as shown in Figure 3. At  $P_{\text{tot}} < 400 \text{ Pa}$ , Al<sub>2</sub>O<sub>3</sub> films in a single phase were prepared although the amounts of Na(dpm) precursors consumed were much more than those of Al(acac)<sub>3</sub> so that  $R_{\text{Na/Al}}$ reached 20–80. That could be due to the severe depletion of Na precursors. At high  $T_{\rm dep}$  such as 1310–1360 K, the Na(dpm) precursor is highly reactive yielding premature reaction in a gas phase often causing powder formation (homogeneous reaction) and the Na(dpm) precursor could have been depleted. However, Na-β-alumina was co-deposited with Al<sub>2</sub>O<sub>3</sub> by increasing  $P_{\text{tot}}$  to 400–600 Pa. It indicated the depletion of Na precursors was compensated by high  $P_{\text{tot}}$  because increasing  $P_{\text{tot}}$  also contributed to a rise of Na concentration in chamber, which favored the formation of Na-Al-O phases. With further increasing  $P_{\text{tot}}$  to 600-1000 Pa, the concentration of gaseous Na precursors in chamber was even raised, causing solitary deposition of Na- $\beta$ -alumina films at  $R_{\text{Na/Al}} = 20-80$ .

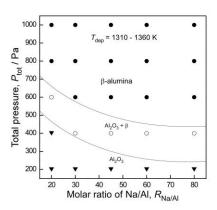


Fig. 3 Effects of  $P_{\text{tot}}$  and  $R_{\text{Na/Al}}$  on the crystalline phases of Na–Al–O films prepared by LCVD.

The (001)-oriented Na- $\beta$ -alumina films deposited at  $P_{\text{tot}} = 600$  Pa consisted of loose flakes. The (110)-oriented Na- $\beta$ -alumina films deposited at  $P_{\text{tot}} = 1000$  Pa had dense facets with polygonal shape. The bright field TEM image of the

Na-β-alumina film at  $P_{\text{tot}} = 1000$  Pa is shown in Fig. 4(a). The platelet grains were elongated from the substrate. Fig. 4(b) depicts the selected area electron diffraction (SAED) pattern corresponding to the grain designated in Fig. 4(a). This indicated that (001) planes of the Na-β-alumina grain were steeply inclined from the substrate as illustrated in Fig. 4(c). The Na-β-alumina film included grains with the conduction planes vertical to the substrate surface, where Na ions were arrayed in the film direction. Since thickness Na ions two-dimensionally migrate along the conduction planes under an electric field, the crystal orientations with the conduction planes parallel to current flows are desirable as electrolytes for batteries.

The maximum  $R_{\text{dep}}$  of NaAlO<sub>2</sub>, NaAl<sub>6</sub>O<sub>9.5</sub> and Na-β-alumina films in a single phase were 131 μm h<sup>-1</sup> at  $T_{\text{dep}} = 986$  K, 46 μm h-1 at  $T_{\text{dep}} = 120$  K at

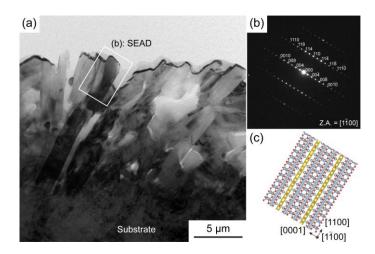


Fig. 4 TEM image (a), electron diffraction pattern (b) and crystal structure perpendicular to (1-10) (c) of Na- $\beta$ -alumina film deposited at  $T_{\rm dep}$ = 1345 K,  $R_{\rm Na/Al}$  = 30 and  $P_{\rm tot}$  = 1000 Pa.

1100 K and 44 μm h<sup>-1</sup> at  $T_{dep} = 1316$  K, respectively. The conductivity of Na-β-alumina film reached 1 S·m<sup>-1</sup> K at 573 K.

## Chapter 5 Preparation of Li-doped Na-Al-O films by laser CVD

In this chapter, variation of crystal phases of Li-doped Na-Al-O films deposited on AlN substrate as functions of  $T_{\rm dep}$  and  $R_{\rm Li/Al}$  was investigated (Fig. 5). Without laser radiation, amorphous films were prepared at  $T_{\rm dep} < 750$  K. At  $T_{\rm dep} = 800$ –900 K and  $R_{\rm Li/Al} = 0$ –0.5, NaAlO<sub>2</sub> was co-deposited with Na<sub>2</sub>CO<sub>3</sub> at  $P_{\rm tot} = 800$  Pa and  $R_{\rm Na/Al} = 1.5$ . Increasing  $T_{\rm dep}$  to 900–1100 K contributed to deposition of NaAlO<sub>2</sub> films in a single phase. With increasing  $R_{\rm Li/Al}$  to 0.5–1.0, the mixture film of NaAlO<sub>2</sub> and LiAlO<sub>2</sub> was prepared at  $T_{\rm dep} = 800$ –1100 K. Further increasing  $R_{\rm Li/Al}$  to 1.5 contributed to formation of LiAlO<sub>2</sub> films in a single phase. At  $T_{\rm dep} = 1100$ –1200 K and  $R_{\rm Li/Al} = 0.1$ –1.0, Li-doped Na-β-alumina was often co-deposited with NaAlO<sub>2</sub>, LiAlO<sub>2</sub>, LiAl<sub>5</sub>O<sub>8</sub>, Al<sub>2</sub>O<sub>3</sub> or NaAl<sub>6</sub>O<sub>9.5</sub>. The strait  $T_{\rm dep}$  range of 1165–1185 K contributed to independent deposition of Li-doped Na-β-alumina films at  $R_{\rm Li/Al} = 0.1$ –0.5. Single-phase Al<sub>2</sub>O<sub>3</sub> films were prepared at  $T_{\rm dep} > 1200$  K.

The mixed film of Li-doped Na-β-alumina and NaAl<sub>6</sub>O<sub>9.5</sub> showed pyramidal grains (Fig. 6(a), (d)). Li-doped Na-β-alumina film consisted of rectangular and triangular facets (Fig. 6(b), (e)). The mixed film of LiAl<sub>5</sub>O<sub>8</sub> and Li-doped Na-β-alumina had clusters of pyramidal grains (Fig. 6(c), (f)). The maximum  $R_{dep}$  (deposition rate) of Li-doped Na-β-alumina films was 60 μm h<sup>-1</sup> at  $T_{dep} = 1167$  K,  $R_{Li/Al} = 0.5$  and  $P_{tot} = 800$  Pa. The as-deposited Li-doped Na-β-alumina film always showed (001) orientation and had low electrical conductivity because the closely-packed spinel structure in the crystal blocked ion movement along c-axis.

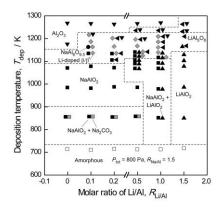


Fig. 5 Effects of  $T_{\text{dep}}$  and  $R_{\text{Li/Al}}$  on the crystalline phases of Li–Na–Al–O films prepared by LCVD.

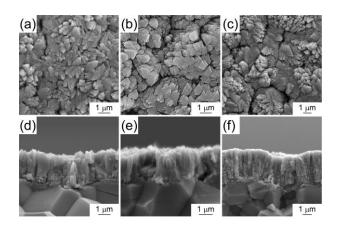


Fig. 6 Microstructures of (a, d) mixture of NaAl<sub>6</sub>O<sub>9.5</sub> and Li-doped  $\beta$ -alumina; (b, e) Li-doped  $\beta$ -alumina film; (c, f) mixture of LiAl<sub>5</sub>O<sub>8</sub> and Li-doped  $\beta$ -alumina.

## **Chapter 6 Conclusions**

Li-Al-O films including LiAl $_5O_8$ , LiAlO $_2$  and Li $_5AlO_4$  were prepared by laser chemical vapor deposition (LCVD). (110)-oriented LiAl $_5O_8$  films had flake-like grains while (100)-oriented LiAl $_5O_8$  films consisted of polygonally faceted grains. (001)-oriented LiAlO $_2$  films showed pyramidal grains and (110)-oriented LiAlO $_2$  films had granular grains. Non-oriented Li $_5AlO_4$  films had dense and rough fluffy morphology. The  $R_{dep}$  reached 98  $\mu$ m h $^{-1}$  at 944 K, where a LiAlO $_2$  and Li $_5AlO_4$  mixed phase was observed. The electrical conductivity of LiAlO $_2$  film is 5 times higher than those of LiAlO $_2$  single crystals and polycrystalline sintered sample at the same temperature.

Na-Al-O films including NaAl<sub>6</sub>O<sub>9.5</sub> and NaAlO<sub>2</sub> were prepared by laser CVD. (041)-oriented NaAl<sub>6</sub>O<sub>9.5</sub> films had polygonal and pyramidal facets. (100)-oriented NaAlO<sub>2</sub> films had finely faceted grains while (110)-oriented NaAlO<sub>2</sub> films showed roof-like grains. The maximum  $R_{dep}$  of NaAlO<sub>2</sub> and NaAl<sub>6</sub>O<sub>9.5</sub> in a single phase were 131  $\mu$ m h<sup>-1</sup> at  $T_{dep}$  = 986 K and 46  $\mu$ m h<sup>-1</sup> at  $T_{dep}$  = 1100 K, respectively.

Beta alumina films including Na-β-alumina and Li-doped Na-β-alumina were obtained by laser CVD. Na-β-alumina films were obtained at  $T_{\rm dep} = 1310$ –1390 K,  $R_{\rm Na/Al} = 20$ –80 and  $P_{\rm tot} = 600$ –1000 Pa. The Na-β-alumina films deposited at  $P_{\rm tot} = 600$  Pa consisted of loose flakes. The (110)-oriented Na-β-alumina films deposited at  $P_{\rm tot} = 1000$  Pa had dense facets with polygonal shape. The maximum  $R_{\rm dep}$  of Na-β-alumina films were 44  $\mu$ m h<sup>-1</sup> at  $T_{\rm dep} = 1316$  K. The electrical conductivity of Na-β-alumina film reached 1 S·m<sup>-1</sup>·K at 573 K. (001)-oriented Li-doped Na-β-alumina films were prepared at  $T_{\rm dep} = 1165$  – 1185 K,  $R_{\rm Li/Al} = 0.1$  – 0.5,  $R_{\rm Na/Al} = 1.5$  and  $P_{\rm tot} = 800$  Pa. The Li-doped Na-β-alumina films consisted of rectangular and triangular facets. The  $R_{\rm dep}$  of Li-doped Na-β-alumina films reached 60  $\mu$ m/h at  $T_{\rm dep} = 1167$  K,  $R_{\rm Li/Al} = 0.5$  and  $P_{\rm tot} = 800$  Pa.

# 論文審査結果の要旨

本論文は、レーザー化学気相析出法(Chemical Vapor Deposition、CVD)を用い Li-Al-O および Na-Al-O 系の酸化物セラミックス材料を合成し、 $\beta/\beta$ "-alumina 構造を有する膜、およびこれらの系に存在する種々の化合物膜を合成し、その合成条件と結晶構造、微細組織および電気的性質を明らかにすることを目的とした研究であり、全 6 章からなる。

第1章および第2章では、研究の背景を述べ、本論文の目的と構成を記した。

第3章では、Li-dipivaloymethanate (Li(dpm))および Al-acetylacetonate (Al(acac)<sub>3</sub>) の有機錯体金属原料を用い、Li-Al-O 膜をレーザー照射場において CVD を行い、CVD 条件が結晶相、微細組織、成膜速度および電気的性質に及ぼす影響を調べた。成膜温度やレーザー強度、炉内圧力や Li/Al 原料供給比を広範な条件で膜を作製し、非晶質 Li-Al-O、LiAlO<sub>2</sub>、LiAl<sub>5</sub>O<sub>8</sub> および Li<sub>5</sub>AlO<sub>4</sub> の各種単相膜およびコンポジット膜が得られた。これらレーザー照射場では、(110)-および(100)-LiAlO<sub>2</sub> 膜や(001)-および(110)-LiAl<sub>5</sub>O<sub>8</sub> 膜など、配向成長することを明らかにした。また、微細組織の炉内圧力や Li/Al 原料供給比による影響を系統的に調べ、粒状組織、ピラミッド自形組織、多角形組織、カリフラワー状組織の Li-Al-O 膜を最大成膜速度約50  $\mu$ m/h で合成した。得られた膜の電気的性質を調べ、LiAlO<sub>2</sub>、LiAl<sub>5</sub>O<sub>8</sub>および Li<sub>5</sub>AlO<sub>4</sub>がイオン伝導性を示すを明らかにした。

第4章では、Li(dpm)および Al(acac)<sub>3</sub> 有機錯体金属原料を用い、Na-Al-O 膜をレーザーCVD により合成し、CVD 条件が結晶相、微細組織、成膜速度および電気的性質に及ぼす影響を調べた。Na/Al 原料供給比 0-3.5 とし、広範な成膜温度および炉内圧力条件で成膜し、非晶質 Na-Al-O、NaAlO<sub>2</sub>、NaAl $_6$ O<sub>9.5</sub> および  $Al_2$ O<sub>3</sub> の単相膜およびコンポジット膜が最大  $100 \mu m/h$ 以上で高速成長した。NaAlO $_2$  および NaAl $_6$ O<sub>9.5</sub> 膜を成膜後に 1373-1573 K で大気焼鈍することで、Na $_6$ / $_6$ "-alumina 膜が得られた。また、Na/Al 原料供給比 20-80、成膜温度 1260 K 以上、炉内圧力 400 Pa 以上の Na 過剰雰囲気下におけるレーザーCVD により Na $_6$ / $_6$ "-alumina が得られることを明らかにした。NaAlO $_2$ 、NaAl $_6$ O $_9.5$  および  $_6$ / $_6$ "-alumina 膜はイオン伝導性を示した。

第5章では、第3および4章で得られた結果を基に、Li 置換した Na $\beta$ / $\beta$ "-alumina 膜の合成を目的とし、レーザーCVD により Li-Na-Al-O 膜を合成した。Na $\beta$ / $\beta$ "-alumina 膜を得るためには Na 過剰雰囲気で 1260 K 以上の高温での合成が必要であったが、では(Li+Na)/Al 原料供給比が 1 以下、成膜温度 1100-1200 K の条件で Li 置換 Na $\beta$ / $\beta$ "-alumina 膜が得られることを明らかにした。Li 置換 Na $\beta$ / $\beta$ "-alumina 膜は、c 軸が基材表面に平行な板状組織をもち、成膜速度は最大で 100  $\mu$ m/h 以上であり、イオン伝導を示すことを明らかにした。

第6章では、本論文を総括した。

よって、本論文は博士(工学)の学位論文として合格と認める。